DB=EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ

☐	L8	(wafer or substrate or semiconductor) same (clean$3 or wash$3) same gate same (ozon$5 with water)	10

DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ

☐	L7	(wafer or substrate or semiconductor) same (clean$3 or wash$3) same gate same (ozon$5 with water)	54
☐	L6	L5 and ((wafer or substrate or semiconductor) same gate same (ozon$5 with water))	2
☐	L5	L4 or 13 or 12 or 11	2280
☐	L4	(macronix international).as.	1196
☐	L3	yang-ling$.in.	41
☐	L2	chen-cheng$.in.	629
☐	L1	huang-chih$.in.	436

END OF SEARCH HISTORY

WEST Search History

DATE: Friday, March 16, 2007

Hide?	Set Name	Query	Hit Count
		DB=PGPB,USPT,USOC; PLUR=YES; OP=ADJ	
☐	L31	L30 and l12	12
☐	L30	l25 and gate	50
☐	L29	l25 same gate	6
		DB=EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ	
☐	L28	L26 and gate	3
☐	L27	L26 same gate	2
☐	L26	(semiconductor or wafer or substrate) same (ozon$5 with water) same ((SC1 or APM or (ammonium hydroxide) or "NH.sub.4OH"))	30
		DB=PGPB,USPT,USOC; PLUR=YES; OP=ADJ	
☐	L25	(semiconductor or wafer or substrate) same (ozon$5 with water) same ((SC1 or APM or (ammonium hydroxide) or "NH.sub.4OH"))	145
☐	L24	(gate with oxide) same (clean$3 or wash$3) same (ozon$5 with water)	22
☐	L23	(gate with oxide) same (clean$3 or wash$3 or etch$3) same (ozon$5 with water)	34
☐	L22	l11 same (SC1 or ammonia or (ammonium hydroxide))	14
		DB=USPT; PLUR=YES; OP=ADJ	
☐	L21	l20 and gate	2
☐	L20	4341592.pn. or 6491763.pn.	2
		DB=PGPB,USPT,USOC; PLUR=YES; OP=ADJ	
☐	L19	l16 and l12	11
☐	L18	L16 and (ozon$5 with water)	2
☐	L17	L16 same (ozon$5 with water)	1
☐	L16	L15 same oxide	81
☐	L15	L14 same (clean$3 or rins$3 or wash$3)	96
☐	L14	(wafer or substrate or semiconductor) with(float$3 adj gate)	13499
☐	L13	L12 and l11	9
☐	L12	l34/2,25.4,26,29,30;438/593,585,591,689,723,724,906.ccls.	12219
☐	L11	(wafer or substrate or semiconductor) same (clean$3 or wash$3) same gate same (ozon$5 with water)	44
☐	L10	(wafer or substrate or semiconductor) same (clean$3 or wash$3) same (gate with float$3) same (ozon$5 with water)	1
☐	L9	(wafer or substrate or semiconductor) same (clean$3 or wash$3) same (gate adj5 float$3) same (ozon$5 with water)	0